Special Issue

Advanced Wide Bandgap Semiconductor Materials and Devices

Message from the Guest Editor

Dear Colleague, Advancements in the field of ultra-wide-bandgap (UWBG) semiconductors are swiftly expanding the horizon of technological possibilities, opening up novel avenues for exploration in electronics, photonics, detection systems, and quantum technology. Semiconductors like gallium oxide, aluminum gallium oxide, diamond, cubic-boron nitride, and aluminum gallium nitride, which boast bandgaps significantly wider than those of gallium nitride (3.4 eV) and silicon carbide (3.3 eV), are leading the charge in cutting-edge material science and the physics of semiconductor devices. We look forward to receiving your contributions.

Guest Editor

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Editor-in-Chief

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